



RECEIVED

JUN 03 2003

TC 1700

1763
AF

503.38156VX1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): YOSHIOKA, et al.

Serial No.: 10/083,353

Filed: February 27, 2002

#9 B NIE

For: APPARATUS FOR PROCESSING SPECIMENS

MW

Group: 1763

#13103
MW

Examiner: K. Moore

AMENDMENT AFTER FINAL REJECTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

June 30, 2003

Sir:

In response to the Office Action mailed March 31, 2003, please amend the above-identified application as follows:

IN THE CLAIMS

Please amend Claims 1 - 2 as follows:

1. (twice amended) An apparatus capable of processing a specimen having two or more layers, at least one of which includes NiFe or NiFeCo alloy, the magnetic property of which is deteriorated if the specimen is heated above 230 °C, and which is laminated on a substrate, the apparatus comprising:

an etching process unit, which is supplied with a gas that can produce a high density gas plasma of a low ion energy with the gas and which can perform etching of the specimen laminated on the substrate, with the produced high density plasma